SUPPORTING INFORMATION

Capillary Wave Confinement Induced Stabilization of Polymer Films

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Supporting Information S1

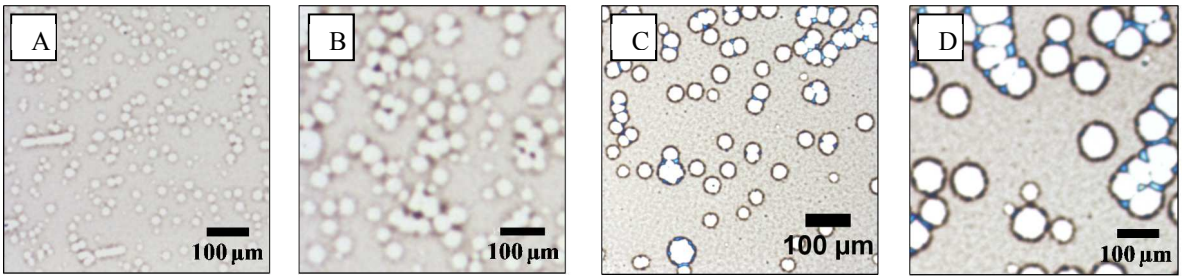

Figure S1. Effect of top-down flexible, unpatterned confinement on PS film stability; optical images of PS films of thickness (A) 30 nm (B) 70 nm (C) 120 nm (D) 220 nm

Supporting Information S2

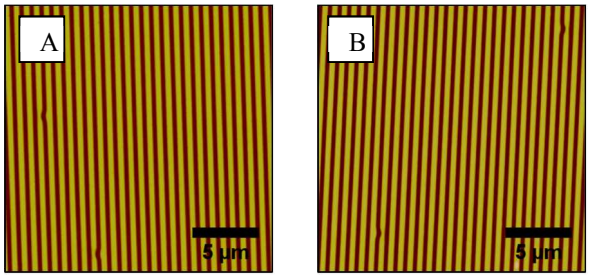

Figure S2. Representative AFM topography images of PS film surfaces following removal of nanopatterned confinement post-annealing (A) 70 nm PS film (B) 120 nm PS film

Supporting Information 3

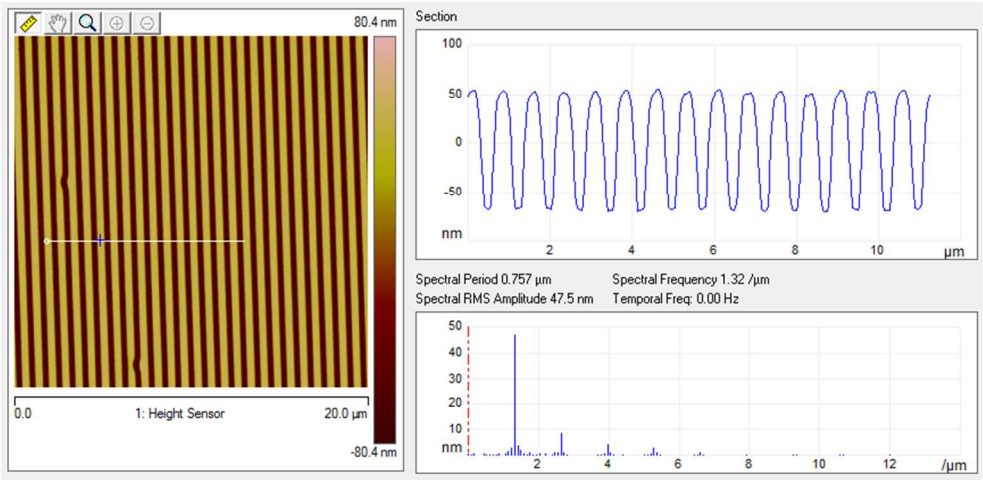

Figure S3. Representative AFM section profile of the topography image of a 120 nm PS film surface confined, during thermal annealing, by DVD patterned PDMS.